



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

: Confirmation No. 8121

Kazuyuki NITTA et al.

: Docket No. 2001-1143A

Serial No. 09/928,430

: Group Art Unit 1752

Filed August 14, 2001

: Examiner S. Lee

POSITIVE-WORKING PHOTORESIST
COMPOSITION AND RESIST PATTERNING
METHOD USING SAME

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEES FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975

SUPPLEMENTAL RESPONSE

Assistant Commissioner for Patents,
Washington, D.C. 20231

Sir:

Further to the Response filed on February 6, 2003, please amend the present application as follows:

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IN THE CLAIMS:

Please amend claim 1 as follows:

1. (Twice Amended) A positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) 100 parts by weight of a hydroxystyrene-based polymer which is a combination of:

(A1) a first polyhydroxystyrene resin having phenolic hydroxyl groups a part of which are substituted for the hydrogen atoms thereof by acid-dissociable alkoxyalkyl groups; and

(A2) a second polyhydroxystyrene resin having phenolic hydroxyl groups a part of which are substituted for the hydrogen atoms thereof by acid-dissociable groups selected from the group consisting of tertiary alkoxy carbonyl groups, tertiary alkyl groups and cyclic ether groups, and